Dr. Dong Gun Lee

(CTO. / ESOL, Inc., Korea)

The speaker is in charge of technology development (CTO) of ESOL, Inc., and received a Ph.D. in the subject of EUV source from KAIST (Korea Advanced Institute of Science and Technology). He had been developing EUV lithography and EUV mask for 16 years at Samsung Electronics' Semiconductor Institute. He conducted joint research with Professor Kinoshita of Japan, the inventor of EUV lithography, for two years. Based on these accumulated experiences and technologies, he is developing equipment for semiconductors using EUV light and optical systems at ESOL, Inc.

A. Education

Period	University	Major	Degree	Advisor
98.03~02.02	KAIST	Physics	Doctor	C. H. Nam
Thesis title: ″Spectral structure analysis of high-order harmoincs and generation of low divergence harmonics″				

B. Work Experience

Period	Affiliation	Position	Subject
19.01~Now	ESOL, Inc.	CTO/Vice president	EUV tool R&D
03.05~18.12	Samsung electronics	Principal engineer	EUV mask and tool R&D
02.03~03.04	Ultra fast laser lab.	Post Doc.	EUV source research

C. Selected Papers

Title	Journal	Year
Coherent control of high-order harmonics with chirped femtosecond laser pulses	Phys. Rev. Lett. (87, 243902)	2001
Selection of high harmonics from a single quantum path for attosecond pulse generation	Phys. Rev. A (63, R021801)	2001
Generation of bright low-divergence high-order harmonics in a long gas jet	Appl. Phys. Lett. (81, 3726)	2002
Wave-front phase measurements of high-order harmonic beams using the point-diffraction interferometry	Opt. Lett. (28, 480)	2003